



## Dr. Jinwoo Kim

HEX A.I. Labs Inc. Korea

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### EDUCATION

**North Carolina State University (NCSU), Raleigh, NC**

Ph.D. in Department of Materials Science and Engineering, 2011

Dissertation: Characterization of Hf Si Oxynitride Pseudo-ternary Gate Dielectrics for the Application of Ge

MOSFETs (Prof. Gerald Lucovsky)

**Hanyang University, Seoul, Korea**

M.S. in Department of Materials Science and Engineering, 2005

Dissertation: Physical, chemical, and electrical characteristics of HfO<sub>2</sub> gate dielectrics and MOSFET grown using the remote- and direct-plasma atomic layer deposition methods (Prof. Hyeongtag Jeon)

**Hanyang University, Seoul, Korea**

Bachelor of Science in Department of Materials Science and Engineering, 2000

### Representative Experiences

**CEO, HEX A.I. Labs Inc.**

Jul. 2024 – Current

**Principal Researcher, Samsung Electronics**

DS division

Feb. 2017 – Jun. 2024

**Research Associate, Univ. of Illinois at Urbana-Champaign**

Jan. 2013 – Feb. 2017

**Postdoc, North Carolina State University**

Physics Department

Jan. 2012 – Dec. 2012

**Researcher, National Institute of Standards and Technology  
(NIST)**

CMOS Reliability and Advanced Devices Group

Apr. 2006 - Mar. 2008

**Researcher, Hynix Semiconductor Inc.**

Memory R&D division

Jan. 2000 - Jan. 2002